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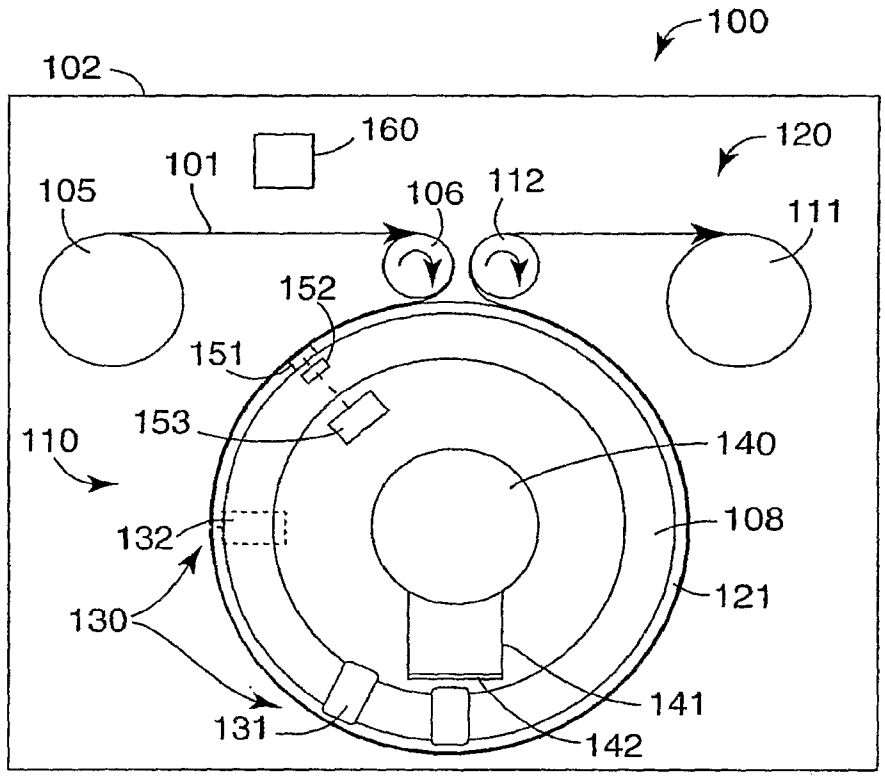
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(54) Title: ROTATABLE APERTURE MASK ASSEMBLY AND DEPOSITION SYSTEM



(57) Abstract: An aperture mask assembly includes a rotatable frame and a mask having apertures. A clamping arrangement is used to tension the mask and to conform the mask to a shape defined by the frame. Tension is applied to the mask in a direction substantially parallel to an axis of the frame and/or around the circumference of the shape defined by the frame. Deposition material emanating from a deposition source located within the rotatable frame is deposited through the mask apertures onto a web.

WO 2007/078556 A1

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